

CORRECTION

[View Article Online](#)
[View Journal](#) | [View Issue](#)Cite this: *Dalton Trans.*, 2021, **50**,
16849**Correction: Mixed H₂O/H₂ plasma-induced redox reactions of thin uranium oxide films under UHV conditions**Ghada El Jamal,^a Thomas Gouder,^b Rachel Eloirdi,^b Evgenia Tereshina-Chitrova,^{c,d}
Lukáš Horák^d and Mats Jonsson*^a

DOI: 10.1039/d1dt90137k

rsc.li/daltonCorrection for 'Mixed H₂O/H₂ plasma-induced redox reactions of thin uranium oxide films under UHV conditions' by Ghada El Jamal *et al.*, *Dalton Trans.*, 2021, DOI: 10.1039/d1dt01020d.

The authors regret an error in the surname of one of the authors, Lukáš Horák, in the original manuscript. In addition, the previous corresponding author Ghada El Jamal has now moved on from her position at KTH Royal Institute of Technology and so the corresponding author for this article has been changed to Mats Jonsson. The corrected list of authors and affiliations for this paper is as shown above.

The Royal Society of Chemistry apologises for these errors and any consequent inconvenience to authors and readers.



^aSchool of Engineering Sciences in Chemistry, Biotechnology and Health (CBH), Department of Chemistry, Applied Physical Chemistry, KTH Royal Institute of Technology, SE-100 44 Stockholm, Sweden. E-mail: matsj@kth.se

^bEuropean Commission, Joint Research Centre, Postfach 2340, DE-76215 Karlsruhe, Germany

^cInstitute of Physics, ASCR, Prague, Czech Republic

^dFaculty of Mathematics and Physics, Charles University, 12116 Prague, Czech Republic